

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):	HWU)	
)	
Filing Date:	Herewith)	
)	
For:	METHOD FOR PATTERN RECOGNITION)	Atty. Docket#: HSJ920030248US1
	IN ENERGIZED CHARGE PARTICLE)	
	BEAM WAFER/SLIDER INSPECTION/)	December 23, 2003
	MEASUREMENT SYSTEM IN PRESENCE)	750 "B" Street, Suite 3120
	OF ELECTRICAL CHARGE)	San Diego, CA 92101

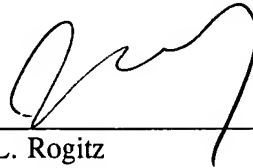
INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Alexandria, VA 22313

Dear Sir:

Pursuant to Sections 1.97, 1.98, and 1.99 of the Rules of Practice in patent cases, enclosed are copies of the references and patents cited on the "List of References Cited by Applicant," Form PTO-1449, submitted herewith.

Respectfully submitted,



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Form PTO-1449

U.S. Department of Commerce
Patent and Trademark Office

Docket No.: HSJ920030248US1

Serial No.: Unk.

Applicant: HWU

Filing Date: Herewith

INFORMATION DISCLOSURE CITATION

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Sub-Class	Filing Date
	US 6,587,581 B1	07/01/03	Matsuyama et al.	382	149	
	US 6,521,890 B2	02/18/03	Ishitani et al.	250	309	
	US 2002/0185597 A1	12/12/02	Ikku et al.	250	309	
	US 6,476,398 B1	11/05/02	Xu et al.	250	396	
	US 2002/0158199 A1	10/31/02	Takane et al.	250	310	
	US 6,332,962 B1	12/25/01	Athas et al.	204	192.34	
	US 5,916,424	06/29/99	Libby et al.	204	298.36	
	US 5,302,828	04/12/94	Monaham	250	307	

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION YES OR NO
	JP7312195	11/28/95	JAPAN	H01J37	22	ABSTRACT
	JP7254387	10/03/95	JAPAN	H01J37	22	YES
	JP2226001	09/07/90	JAPAN	G01B11	00	ABSTRACT

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Saitoh, K.; Takeuchi, S.; Moriizumi, K.; Watakabe, Y.; Kato, T.; "Electron beam pattern inspection system using digital image processing". J. Vac. Sci. Technol. B; 4(3), pp. 686-691 (May 1986)
	Osamu Nasu; Katsuhiro Sasada; Mitsuji Ikeda; Makoto Ezumi; "New CD-SEM System for 100-nm Node Process". Hitachi Rev. 51(4) pp.125-129 (2002).
	KLA Tencor brochure (2003)
	Kurt Laken; "Advanced Pole Analysis: A New Tool for Measuring Pole Tip Recession". VEECO Brochure (2002)

Examiner:

Date Considered:

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.